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(54) **METHOD OF FORMING
LIGHT-GENERATING DEVICE INCLUDING
REFLECTIVE LAYER**

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CPC **H01L 33/60** (2013.01); **H01L 33/08**
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USPC 257/88; 438/29

See application file for complete search history.

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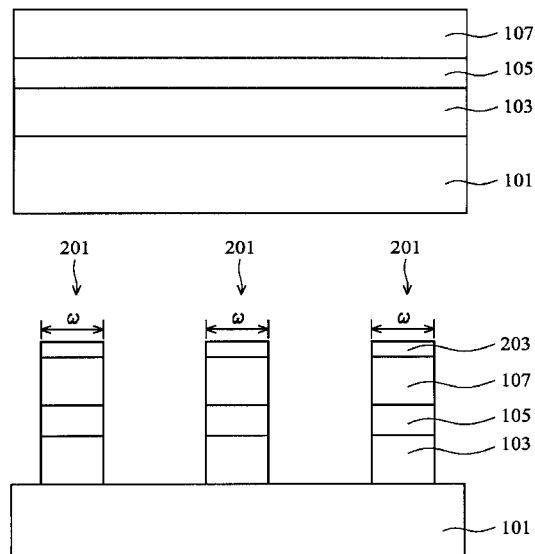
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(57) **ABSTRACT**

A system and method for manufacturing a light-generating device is described. A preferred embodiment comprises a plurality of LEDs formed on a substrate. Each LED preferably has spacers along the sidewalls of the LED, and a reflective surface is formed on the substrate between the LEDs. The reflective surface is preferably located lower than the active layer of the individual LEDs.

16 Claims, 5 Drawing Sheets



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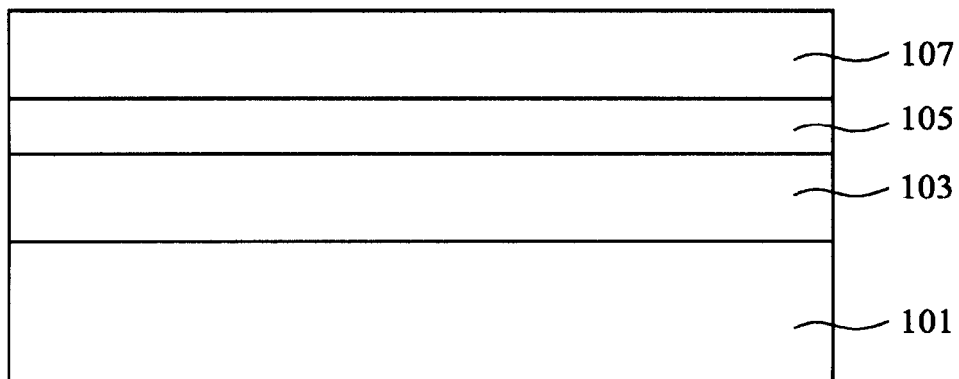


Figure 1

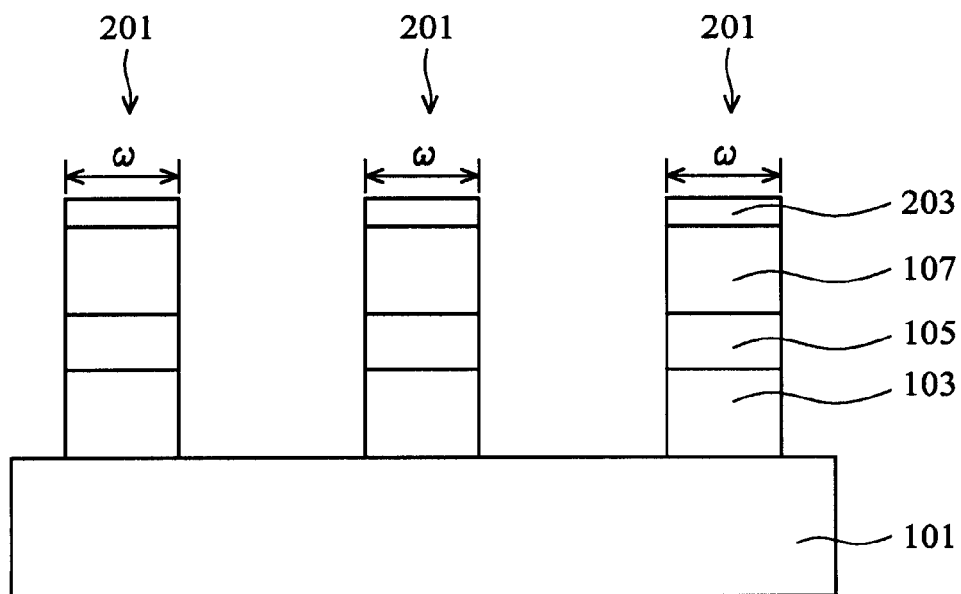


Figure 2

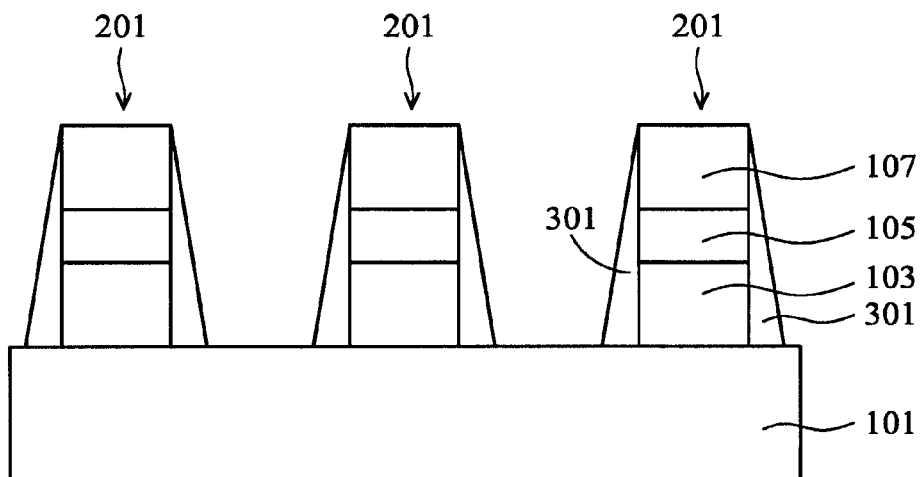


Figure 3

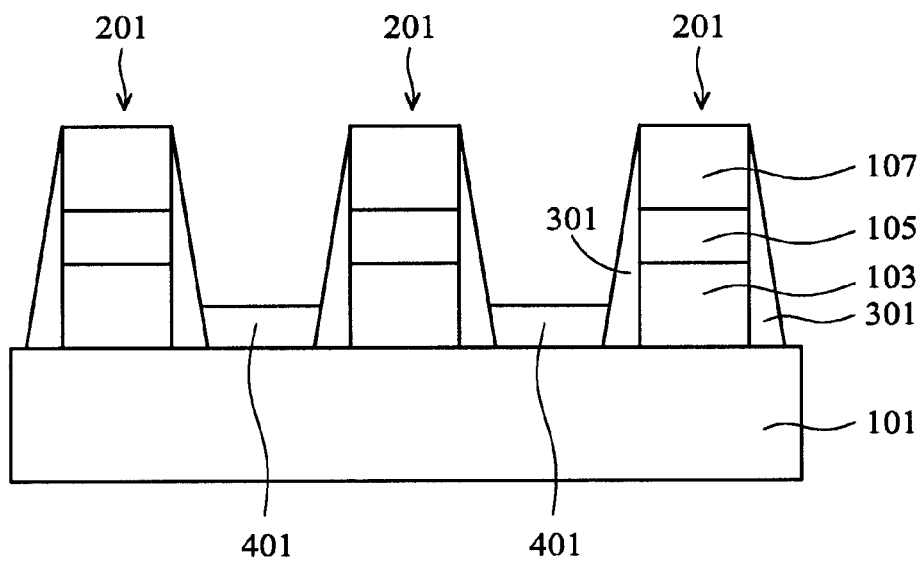


Figure 4

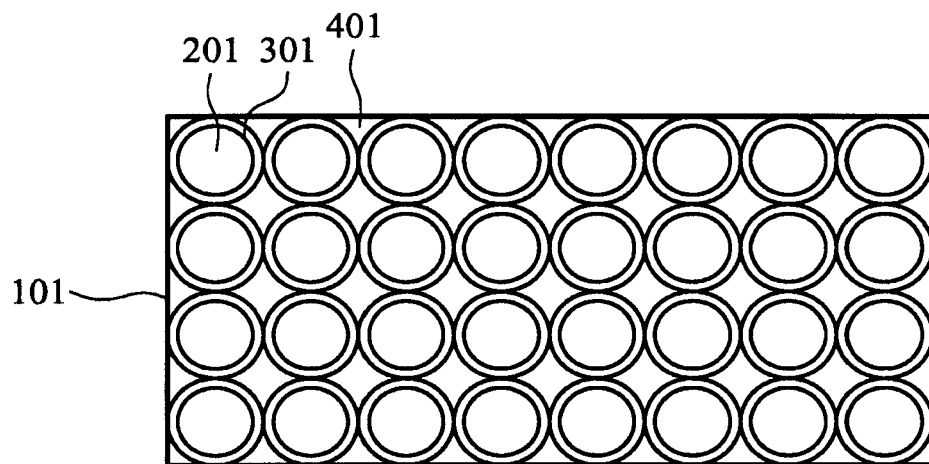


Figure 5A

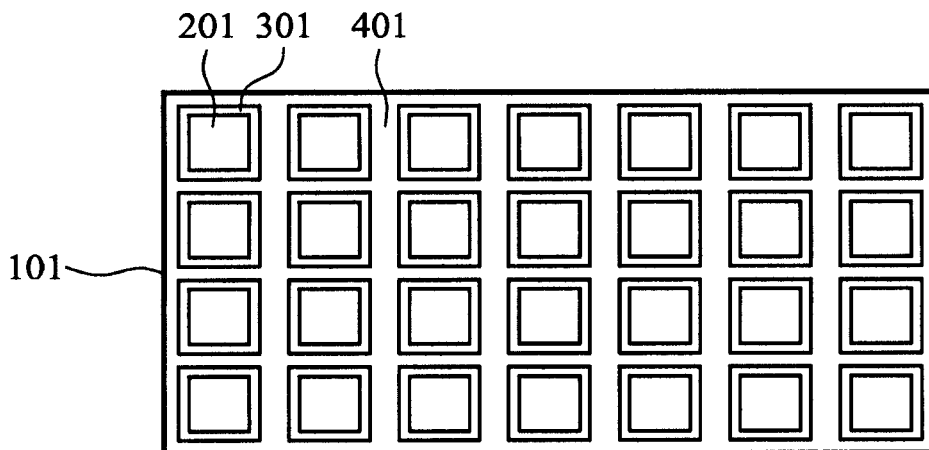


Figure 5B

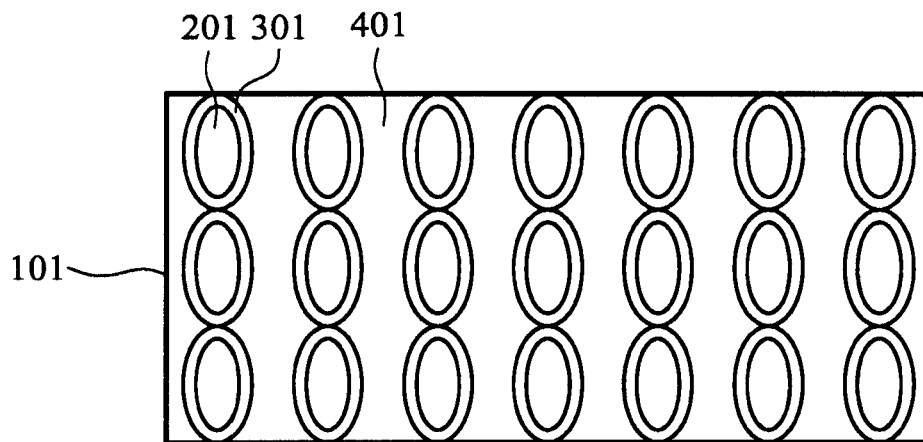


Figure 5C

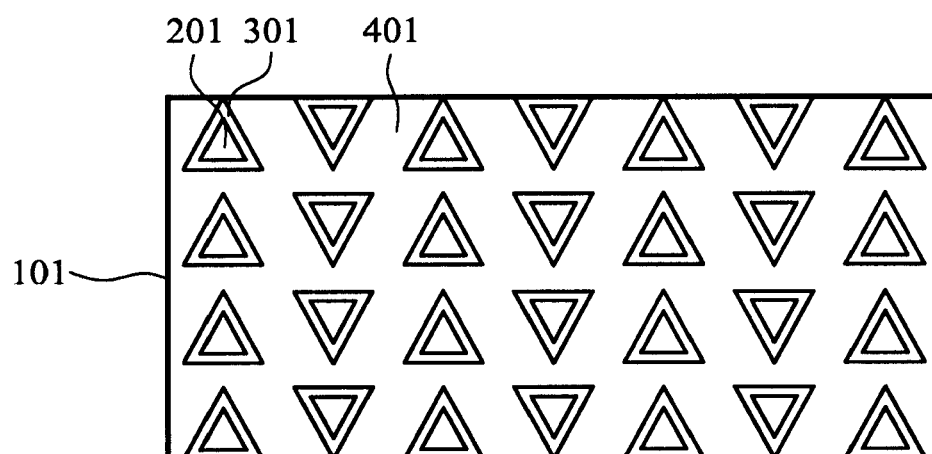


Figure 5D

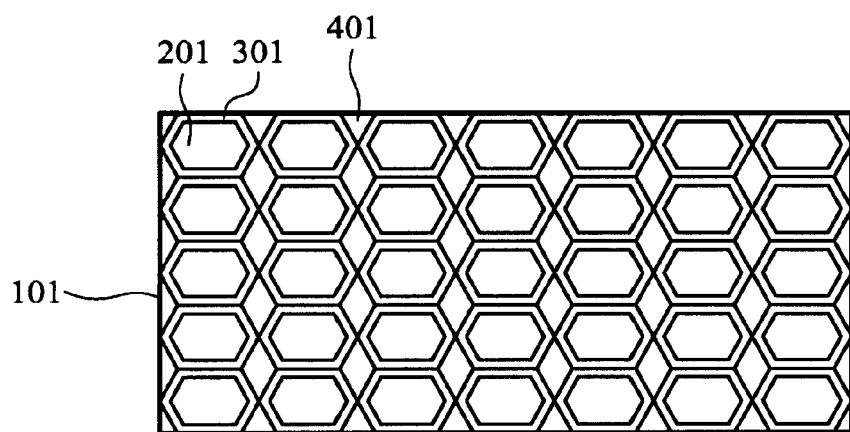


Figure 5E

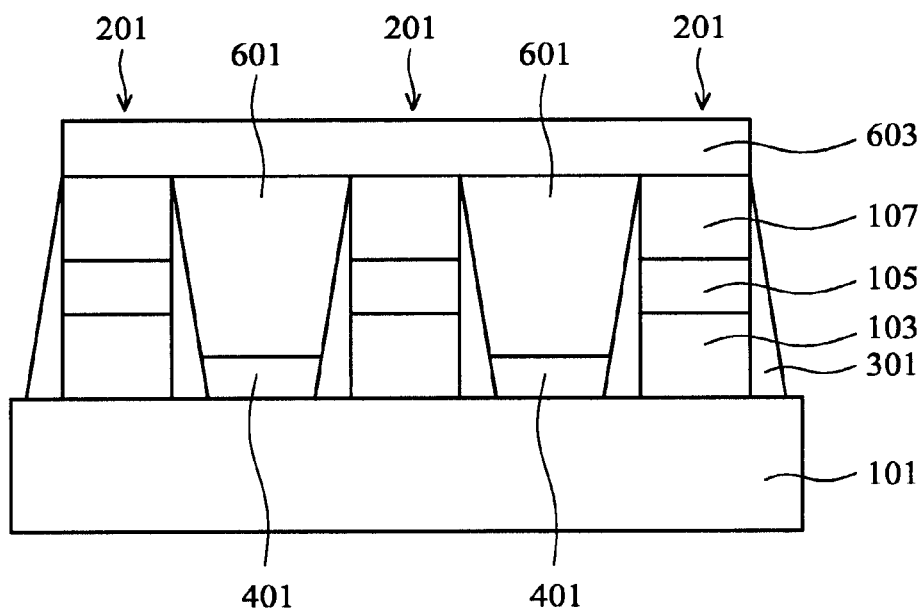


Figure 6

1

METHOD OF FORMING LIGHT-GENERATING DEVICE INCLUDING REFLECTIVE LAYER

PRIORITY DATA

The present application is a divisional application of U.S. patent application Ser. No. 12/270,309, filed on Nov. 13, 2008, now U.S. Pat. No. 8,716,723 issued May 6, 2014, which claims the benefit of U.S. Provisional Patent Application No. 61/089,755, filed on Aug. 18, 2008, both entitled "Reflective Layer for Light-Emitting Diodes," incorporated herein by reference in their respective entireties.

TECHNICAL FIELD

The present invention relates generally to a system and method for manufacturing light-emitting diodes (LEDs) and, more particularly, to a system and method for manufacturing LEDs with a reflective layer.

BACKGROUND

Generally, light-emitting diodes (LEDs) are formed using a diode with a first contact layer, an active layer, and a second contact layer on a substrate. When these layers are forward biased, light at various wavelengths can be generated, which then propagates outward in multiple directions. Some of these directions may be undesired, such as when the light is intended to propagate in a particular direction, or the light impacts a light-absorbing material (such as a silicon substrate), which decreases the overall luminosity of the LED.

These problems of luminosity and directionality have been treated by such methods as placing a distributed Bragg reflector (DBR) beneath the active layer of the LED to reflect the light away from the substrate. However, DBRs become less efficient reflectors at higher incident angles relative to normal to the surface of the DBRs. Additionally, some light may not even impact a DBR as the light escapes the LEDs and propagates toward the substrate, which may absorb the light and prevent its reflection.

Another solution has been to use a light transmissive substrate such as sapphire and form a reflective layer on an opposite side of the substrate from the LEDs. However, this procedure limits the materials available for LED substrates to light transmissive substrates such as sapphire, and prevents the usage of more preferred substrates such as silicon. This can lead to more complicated and expensive manufacturing processes.

Accordingly, what is needed is a structure that allows for the use of more materials for substrates without a corresponding absorption of light.

SUMMARY OF THE INVENTION

These and other problems are generally solved or circumvented, and technical advantages are generally achieved, by preferred embodiments of the present invention which provide a reflective surface between LEDs.

In accordance with a preferred embodiment of the present invention, a light-emitting device comprises a substrate, a first LED with a first active layer on the substrate, and a second light-emitting diode with a second active layer on the substrate. A reflective layer is located on the substrate between the first light-emitting diode and the second light-emitting diode, and the reflective layer comprises a top surface that is closer to the substrate than the first active layer.

2

In accordance with another preferred embodiment of the present invention, a light-generating device comprises a substrate and a reflective layer over portions of the substrate, the reflective layer having a first thickness. A plurality of light-emitting diodes extends through the reflective layer to the substrate, each of the plurality of light-emitting diodes comprising an active layer that is located a first distance from the substrate, the first distance being greater than the first thickness.

In accordance with yet another preferred embodiment of the present invention, a method for forming a light-generating device comprises providing a substrate and forming a plurality of light-emitting diodes on the substrate, each of the light-emitting diodes comprising an active layer. A reflective layer is formed on the substrate between the plurality of light-emitting diodes and below the active layer.

An advantage of a preferred embodiment of the present invention is the enhancement of the light output of the devices incorporating the reflector. Preferred embodiments also allow for the use of light-absorbing materials as a substrate for the LEDs.

BRIEF DESCRIPTION OF THE DRAWINGS

FIG. 1 illustrates the formation of a first contact layer, an active layer, and a second contact layer over a substrate in accordance with an embodiment of the present invention;

FIG. 2 illustrates the patterning of the first contact layer, the active layer, and the second contact layer into individual LEDs in accordance with an embodiment of the present invention;

FIG. 3 illustrates the formation of spacers along the side-walls of the LEDs in accordance with an embodiment of the present invention;

FIG. 4 illustrates the formation of a reflective thin film along the substrate between the LEDs in accordance with an embodiment of the present invention;

FIGS. 5A-5E illustrate plan views of various shapes of the individual LEDs in accordance with an embodiment of the present invention; and

FIG. 6 illustrates the formation of a top electrode over the LEDs in accordance with an embodiment of the present invention.

Corresponding numerals and symbols in the different figures generally refer to corresponding parts unless otherwise indicated. The figures are drawn to clearly illustrate the relevant aspects of the preferred embodiments and are not necessarily drawn to scale.

DETAILED DESCRIPTION OF ILLUSTRATIVE EMBODIMENTS

The making and using of the presently preferred embodiments are discussed in detail below. It should be appreciated, however, that the present invention provides many applicable inventive concepts that can be embodied in a wide variety of specific contexts. The specific embodiments discussed are merely illustrative of specific ways to make and use the invention, and do not limit the scope of the invention.

The present invention will be described with respect to preferred embodiments in a specific context, namely a reflective layer for multiple LEDs. The invention may also be applied, however, to other reflective layers.

With reference now to FIG. 1, there is shown a substrate **101**, a first contact layer **103**, an active layer **105**, and a second contact layer **107**. The substrate **101** is preferably a sapphire or semiconductor substrate. It should be noted that while

embodiments of the present invention are described in the context of using a bulk silicon substrate, other substrates may be used. For example, silicon-on-insulator (SOI) substrates, SiC substrates, MgAl_2O_4 substrates, and the like may also be used. Embodiments of the present invention, however, may be particularly suited to silicon substrates due to the low cost in addition to reducing the residual stress in the LED structure formed thereon. Furthermore, while a substrate having a (111) surface orientation is preferred, substrates having a different surface orientation, such as (100) and (110) surface orientations, may also be used. Silicon substrates may also improve the extraction efficiency and allow a selective group III-N epitaxial growth process to be used.

The first contact layer **103** is preferably formed over the substrate **101**. The first contact layer **103** preferably forms one part of the diode required to emit light, and preferably comprises a group III-V compound. As the name implies, group III-V compounds comprise a group III element and a group V element and include compounds such as GaN, InN, AlN, $\text{Al}_x\text{Ga}_{(1-x)}\text{N}$, $\text{Al}_x\text{In}_{(1-x)}\text{N}$, $\text{Al}_x\text{In}_y\text{Ga}_{(1-x-y)}\text{N}$, combinations thereof, or the like. In an embodiment in which p-up LEDs are being formed, the first contact layer **103** is preferably doped with a dopant of an n-type conductivity type (e.g., n-GaN). However, p-type dopants may alternatively be used, depending upon the desired conductivity of the first contact layer **103** to form an n-up LED.

The first contact layer **103** is preferably formed, for example, through an epitaxial growth process such as molecular beam epitaxy (MBE), although other processes, such as hydride vapor phase epitaxy (HVPE), liquid phase epitaxy (LPE), or the like, may alternatively be utilized. The first contact layer **103** is preferably formed to have a thickness of between about 1 μm and about 6 μm , with a preferred thickness of about 2 μm . The first contact layer **103** is preferably doped in situ during formation to a concentration of between about $1 \times 10^{16} \text{ cm}^{-3}$ and about $1 \times 10^{19} \text{ cm}^{-3}$, with a preferred dopant concentration of about $1 \times 10^{18} \text{ cm}^{-3}$, although other processes, such as ion implantation or diffusion may alternatively be utilized.

The active layer **105** is preferably formed over the first contact layer **103**. The active layer **105** is designed, among other things, to control the generation of light to desired wavelengths. For example, by adjusting and controlling the proportional composition of the elements in the active layer **105**, the bandgap of the materials in the active layer **105** may be adjusted, thereby adjusting the wavelength of light that will be emitted by the LED.

The active layer **105** preferably comprises multiple quantum wells (MQW). MQW structures in the active layer **105** may comprise, for example, layers of InGa N , Ga N , $\text{Al}_x\text{In}_y\text{Ga}_{(1-x-y)}\text{N}$ (where $0 < x < 1$), or the like. The active layer **105** may comprise any number of quantum wells, 5 to 20 quantum wells for example, each preferably about 30 to about 100 Å thick. The MQWs are preferably epitaxially grown using the first contact layer **103** as a nucleation layer using metal organic chemical vapor deposition (MOCVD), although other processes, such as MBE, HYPE, LPE, or the like, may alternatively be utilized.

The second contact layer **107** is preferably formed over the active layer **105**. The second contact layer **107** preferably forms the second part of the diode required to emit light in conjunction with the first contact layer **103**. The second contact layer **107** preferably comprises a group III-V compound such as GaN, InN, AlN, $\text{Al}_x\text{Ga}_{(1-x)}\text{N}$, $\text{Al}_x\text{In}_{(1-x)}\text{N}$, $\text{Al}_x\text{In}_y\text{Ga}_{(1-x-y)}\text{N}$, combinations thereof, or the like, doped with a dopant of a second conductivity type (e.g., p-GaN) opposite the first conductivity type in the first contact layer **103**.

The second contact layer **107** is preferably formed, for example, through an epitaxial growth process such as MOCVD. Other processes, however, such as HYPE, LPE, MBE, or the like, may alternatively be utilized. The second contact layer **107** is preferably formed to have a thickness of between about 0.1 μm and about 2 μm , with a preferred thickness of about 0.3 μm and is preferably doped in situ to a concentration of between about $1 \times 10^{17} \text{ cm}^{-3}$ and about $1 \times 10^{21} \text{ cm}^{-3}$, with a preferred dopant concentration of about $1 \times 10^{19} \text{ cm}^{-3}$, although other processes, such as ion implantation or diffusion, may alternatively be utilized.

FIG. 2 illustrates the patterning of the first contact layer **103**, the active layer **105**, and the second contact layer **107** to form a plurality of LEDs **201**. These LEDs **201** are preferably micro and nano-sized LEDs **201** that have a width comparable with the wavelength of the light that will be emitted. For example, while the LEDs **201** preferably have a width of between about 10 nm and about 10 μm , with a preferred width of about 250 nm, the LEDs **201** even more preferably have a width of between about 0.3 to about 3 times the wavelength of the light that will be emitted from the LEDs **201**, such as 250 nm for light with a wavelength of 480 nm. In this embodiment in which the width of the nano-sized LEDs **201** is comparable to the wavelength of the emitted light, the downward-propagating light will not be substantially confined within the nano-sized LEDs **201**, thereby leading to even more light being emitted from the LEDs **201**.

The first contact layer **103**, the active layer **105**, and the second contact layer **107** are preferably patterned by forming a hard mask **203** from a material such as silicon nitride, silicon oxide, a metal such as nickel, combinations of these, or the like over the second contact layer **107**. The hard mask **203** is preferably formed by blanket depositing a hard mask layer (not shown) over the second contact layer **107**. A suitable photolithographic process is then preferably used to pattern the hard mask layer into the hard mask **203** and to expose those portions of the second contact layer **107** that are desired to be removed to form the LEDs **201** as illustrated in FIG. 2. Other processes, however, such as a photolithographic mask or nanoimprint, may alternatively be used to protect and pattern the first contact layer **103**, the active layer **105**, and the second contact layer **107**.

Once the hard mask **203** has been formed and patterned, an etching process is preferably performed to form the pillars of the LEDs **201**. An etching process such as a dry etch may be used to remove those portions of the second contact layer **107**, the active layer **105**, and the first contact layer **103** that have been left exposed by the hard mask **203**. Preferably, this etching is performed to remove the first contact layer **103**, the active layer **105**, and the second contact layer **107** in a single etching step, although multiple etching processes may alternatively be used to form the LEDs **201**.

FIG. 3 illustrates the formation of spacers **301** and the removal of the hard mask **203**. The spacers **301** preferably prevent the first contact layer **103** from electrically shorting to the second contact layer **107** and are typically formed by initially blanket depositing a spacer layer (not shown) on the previously formed structure. The spacer layer preferably comprises a material such as Si N , ox nitride, SiC, Si O_2 , oxide, and the like. The spacer layer is preferably formed by commonly used methods such as chemical vapor deposition (CVD), plasma enhanced CVD, sputter, and other methods known in the art and is then patterned to form the spacers **301**, preferably by anisotropically etching to remove the spacer layer from the horizontal surfaces of the LEDs **201** and the substrate **101**.

5

Once the spacers **301** have been formed, the hard mask **203** is preferably removed from the upper surfaces of the second contact layer **107**. Preferably, the hard mask **203** is removed using a wet etch that is selective to the material of the hard mask (e.g., silicon nitride or nickel) while not substantially removing material from the LEDs **201** or the substrate **101**. Alternatively, a grinding process such as CMP, or a combination of etching and grinding, may alternatively be used to remove the hard mask **203**.

FIG. **4** illustrates the formation of a reflective layer **401** along the substrate **101** between the individual LEDs **201** and below the level of the active layer **105**. The reflective layer **401** preferably comprises a high-reflective metal such as aluminum, silver, or the like, although any suitably reflective material may alternatively be used. The reflective layer **401** is preferably formed by initially forming a blanket layer of high-reflective metal through a process such as physical vapor deposition (PVD), although other processes, such as CVD or sputtering, may alternatively be used, and then etching undesired portions of the blanket layer using a suitable photolithographic process to form the reflective layer **401**. The reflective layer **401** is preferably formed to be at least 10 nm thick, but is also preferably formed to be lower than the active layer **105** of the LEDs **201**, so preferably has a thickness no greater than the distance between the substrate **101** and the lower portion of the active layer **105**.

By preferably forming the reflective layer **401** along the substrate **101** between the individual LEDs **201** and below the active layer **105**, any light that escapes from the individual LEDs **201** that is propagating toward the substrate **101** may be reflected prior to impinging upon the substrate **101**. If the substrate **101** is a light absorbing substrate **101**, such as silicon, the reflective layer **401** will increase the overall luminosity of the LEDs **201** as the light will be reflected instead of being absorbed. Additionally, the reflective layer **401** may be used to direct light in a certain direction (e.g., away from the substrate **101**), and away from undesired directions.

FIGS. **5A-5E** illustrate plan views of multiple LEDs **201**, their associated spacers **301**, and the reflective layer **401**. While the shape of the individual LEDs **201** may be any shape, FIG. **5A** illustrates a preferred embodiment in which the LEDs **201** are circular. In this embodiment the circular LEDs **201** preferably have a diameter of between about 10 nm and about 5,000 nm, with a preferred diameter of about 250 nm. The individual LEDs **201** are also preferably arranged in a grid pattern, with a pitch of between about 10 nm and about 10 μ m, with a preferred pitch of about 250 nm, although other layouts, such as a staggered layout, may alternatively be used.

FIG. **5B** illustrates another preferred embodiment in which the LEDs **201** are rectangular in shape. In this embodiment, the LEDs **201** are also preferably arranged in a grid pattern with the reflective layer **401** between the individual LEDs **201**. The rectangular LEDs **201** also preferably have a length of between about 10 nm and about 5,000 nm, with a preferred length of about 10 μ m, a width of between about 10 nm and about 5,000 nm, with a preferred width of about 250 nm, and a spacing between the LEDs **201** of between about 10 nm and about 5,000 nm, with a preferred spacing of about 250 nm.

FIG. **5C** illustrates yet another preferred embodiment in which the LEDs **201** are elliptical in shape. In this embodiment, the elliptical LEDs **201** are preferably, but not necessarily, arranged in a grid pattern, with a preferred spacing between the LEDs **201** of between about 10 nm and about 10 μ m, with a preferred spacing of about 250 nm.

FIG. **5D** illustrates yet another preferred embodiment in which the LEDs **201** are triangular in shape. In this embodiment, the triangular LEDs **201** are preferably arranged in

6

rows and columns, although the LEDs **201** could alternatively be staggered. The LEDs **201** in this embodiment preferably have a pitch of between about 10 nm and about 10 μ m, with a preferred pitch of about 250 nm, and the triangular LEDs **201** preferably have a side length of between about 10 nm and about 5,000 nm, with a preferred side length of about 250 nm.

FIG. **5E** illustrates yet another preferred embodiment in which the LEDs **201** are hexagonal in shape. In this embodiment, the hexagonal LEDs **201** are preferably arranged in rows and columns, although the LEDs **201** may alternatively be staggered so as not to align with each other. In this embodiment the LEDs **201** preferably have a pitch of between about 10 nm and about 10 μ m, with a preferred pitch of about 250 nm.

FIG. **6** illustrates the filling of the area above the reflective layer **401** and between the LEDs **201** with a fill material **601** and the formation of a top electrode **603**. The fill material **601** preferably comprises a material that is transparent to LED radiation (e.g., visible light), such as silicon dioxide, and is preferably formed by, for example, chemical vapor deposition (CVD) techniques using tetra-ethyl-ortho-silicate (TEOS) and oxygen as precursors. However, other materials, such as silicon nitride, silicon oxynitride, or the like, and other processes, such as plasma enhanced CVD, may alternatively be used.

Preferably, the fill material **601** is formed so as to overfill the areas between the LEDs **201** and above the reflective layer **401**. Excess fill material **601** is then removed through a grinding process, such as chemical mechanical polishing (CMP), so as to expose the second contact layer **107**. Other removal processes, however, such as etching or a combination of etching and grinding, may alternatively be used to remove the excess fill material **601**.

Once the excess fill material **601** has been removed and the second contact layer **107** has been substantially exposed, a top electrode **603** is formed in electrical contact with the second contact layer **107** of one or more of the LEDs **201**. The top electrode **603** is preferably formed of a transparent, conductive material such as a thin layer of nickel, a thin layer of gold, a transparent conductive oxide, combinations of these, or the like, and may be formed through a process such as PVD, sputtering, CVD, or the like. The top electrode **603** preferably has a thickness of between about 10 Å and about 1,000 Å, with a preferred thickness of about 100 Å.

Thereafter, processes may be performed to complete the LEDs **201**. For example, electrical contacts may be formed to the first contact layer **103** in each LED **201**, either through a conductive substrate **101** or else through the formation of another contact in cases when the substrate is non-conductive. Eventually, the LED device may be diced and packaged.

It should also be noted that the above description describes a method of forming LEDs with a reflective surface between the LEDs. Other layers, such as a distributed Bragg reflector or a buffer layer, may be desirable as part of the individual LEDs **201**. Depending upon the type of substrate **101** and the connections to the first and second contact layers **103** and **107**, respectively, a buffer layer may also be desirable between the first contact layer **103** and the substrate **101**. For example, with some types of substrates, such as SiC and Si substrates, a buffer layer, such as AlN or AlGaN, may be desirable to aid in the epitaxial growth of a group III-N compound on the SiC substrate. A distributed Bragg reflector generally comprises multiple layers having different refractive indices that cause light emitted from the LEDs to be reflected, thereby increasing the light emitted from the top of the LEDs **201**. A reflective buffer layer may also be used with or in place of the distributed Bragg reflector.

The structure of the LEDs **201** may also vary depending on the type of materials used and the intended application. It is expected that many types of LED structures may be used with embodiments of the present invention, which provides a reflective surface between the LEDs **201**.

Although the present invention and its advantages have been described in detail, it should be understood that various changes, substitutions and alterations can be made herein without departing from the spirit and scope of the invention as defined by the appended claims. For example, buffer layers or distributed Bragg reflectors may be used in conjunction with the LEDs. As another example, it will be readily understood by those skilled in the art that various materials and processes may be varied while remaining within the scope of the present invention.

Moreover, the scope of the present application is not intended to be limited to the particular embodiments of the process, machine, manufacture, composition of matter, means, methods and steps described in the specification. As one of ordinary skill in the art will readily appreciate from the disclosure of the present invention, processes, machines, manufacture, compositions of matter, means, methods, or steps, presently existing or later to be developed, that perform substantially the same function or achieve substantially the same result as the corresponding embodiments described herein may be utilized according to the present invention. Accordingly, the appended claims are intended to include within their scope such processes, machines, manufacture, compositions of matter, means, methods, or steps.

What is claimed is:

1. A method of forming a light-generating device, comprising:

forming a plurality of light-emitting diodes (LEDs) over a substrate, the LEDs each including a first group III-V compound layer, a second group III-V compound layer, and an active layer disposed between the first group III-V compound layer and the second group III-V compound layer, wherein the LEDs are physically separated from one another;

forming spacers on side surfaces of each of the LEDs; and thereafter forming a reflective material over portions of the substrate that are not covered by the LEDs and the spacers, wherein the reflective material is formed below the active layer of the LEDs.

2. The method of claim **1**, further comprising:

forming a dielectric layer over the reflective material; and forming a conductive layer over the dielectric layer and over the LEDs.

3. The method of claim **2**, wherein the forming of the conductive layer is performed such that the LEDs are electrically coupled together by the conductive layer.

4. The method of claim **2**, wherein the forming of the dielectric layer and the forming of the conductive layer are performed such that the dielectric layer and the conductive layer are each transparent.

5. The method of claim **4**, wherein:

the dielectric layer contains silicon oxide, silicon nitride, or silicon oxynitride; and

the conductive layer contains a thin layer of nickel, a thin layer of gold, or a transparent conductive oxide.

6. The method of claim **4**, wherein the conductive layer has a thickness in a range from about 10 angstroms to about 1000 angstroms.

7. The method of claim **1**, wherein the forming of the plurality of LEDs comprises:

growing the first group III-V compound layer over the substrate;

growing the active layer over the first group III-V compound layer;

growing the second group III-V compound layer over the active layer; and

5 patterning the second group compound layer, the active layer, and the first group III-V compound layer into the plurality of LEDs.

8. The method of claim **7**, wherein the patterning is performed such that a lateral dimension of each LED is between about 0.3 to about 3 times a wavelength of a light emitted by said LED.

9. A method of forming a light-generating device, comprising:

forming a first group III-V compound layer over a substrate;

forming an active layer over the first group III-V compound layer;

forming a second group III-V compound layer over the active layer;

20 patterning the second group III-V compound layer, the active layer, and the first group III-V compound layer into a plurality of nano-sized LEDs, wherein a ratio of a lateral dimension of each nano-sized LED and a wavelength of a light emitted by the nano-sized LED is in a range from about 0.3 to about 3;

forming spacers on sidewalls of the LEDs; and

thereafter forming a reflective material over the substrate and between the spacers.

10. The method of claim **9**, wherein the forming of the reflective material is performed such that a thickness of the reflective material is less than a distance between the substrate and the active layer.

11. The method of claim **9**, wherein the nano-sized LEDs are separated by a plurality of gaps, and further comprising filling the gaps with a transparent material.

12. The method of claim **11**, further comprising forming a top electrode layer over the transparent material and over the nano-sized LEDs, wherein the top electrode layer is electrically coupled to the nano-sized LEDs.

13. The method of claim **12**, wherein the top electrode layer is formed to be transparent and have a thickness in a range from about 10 angstroms to about 1000 angstroms.

14. A method for forming a light-generating device, the method comprising:

providing a substrate;

forming a plurality of light-emitting diodes on the substrate, each of the plurality of light-diodes comprising an active layer; and

forming a reflective layer on the substrate,

wherein the reflective layer is located between adjacent ones of the plurality of light emitting diodes and below the active layers, and

wherein the forming a reflective layer includes forming spacers along sidewalls of the plurality of light-emitting diodes and filling an area between the spacers and over the reflective layer with a light-transmissive material.

15. The method of claim **14**, further comprising planarizing the light-transmissive material, the planarizing step also substantially exposing top surfaces of the plurality of light-emitting diodes.

16. A method for forming a light-generating device, the method comprising:

providing a substrate;

forming a plurality of light-emitting diodes on the substrate, each of plurality of light-emitting diodes comprising an active layer; and

forming a reflective layer on the substrate,

wherein the reflective layer is located between adjacent ones of the plurality of light-emitting diodes and below the active layers, and

wherein the forming a plurality of light-emitting diodes comprises:

forming a first contact layer;

forming an active layer over the first contact layer;

forming a second contact layer over the active layer;

forming a hard mask over the second contact layer, the

hard mask exposing portions of the second contact layer; and

etching the exposed portions of the second contact layer, the active layer, and the first contact layer to form the plurality of light-emitting diodes.

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15